

Supporting Information

Multilayer Heterostructure Engineering for Ultrapure and Area Emission in Perovskite Quantum-Dot Light-Emitting Transistors

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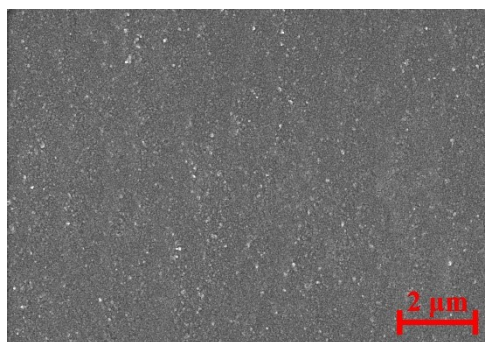


Figure S1. The SEM image of the CsPbBr₃ QD film spin-coated on the ZTO.

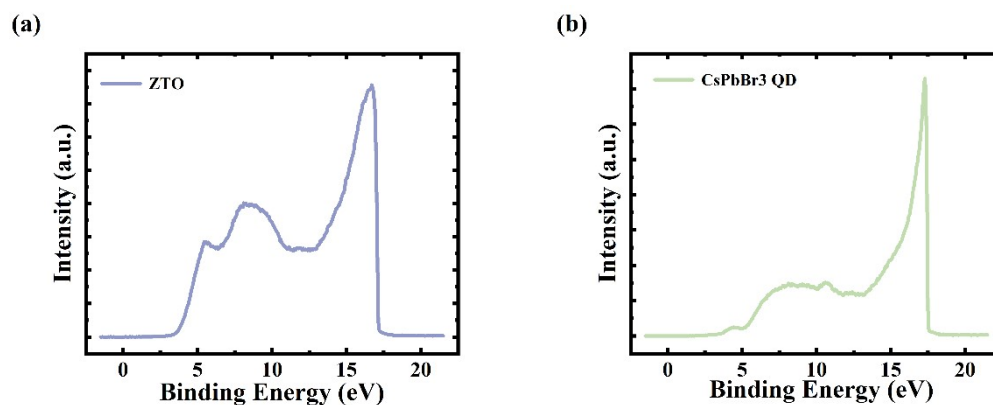


Figure S2. UPS spectra of the ZTO film and CsPbBr₃ QD film.

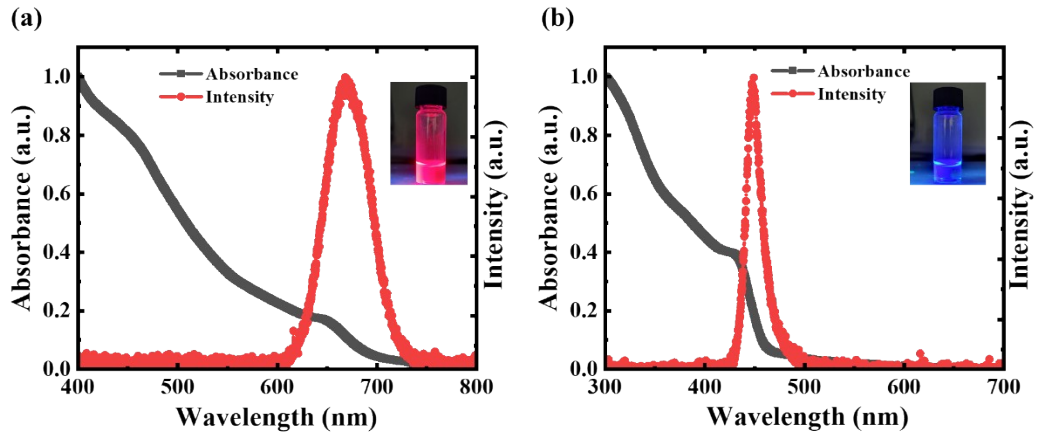


Figure S3. (a) Absorption spectra and PL spectra of the synthesized CsPbI₃ perovskite QD dispersion. (b) Absorption spectra and PL spectra of the synthesized CsPbBr_xCl_{3-x} perovskite QD dispersion.

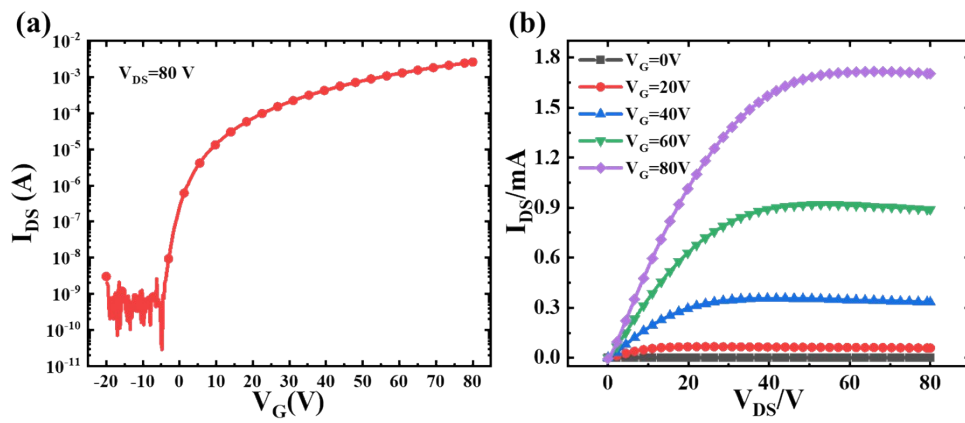


Figure S4. ZTO field-effect transistor transfer curve and output curve.

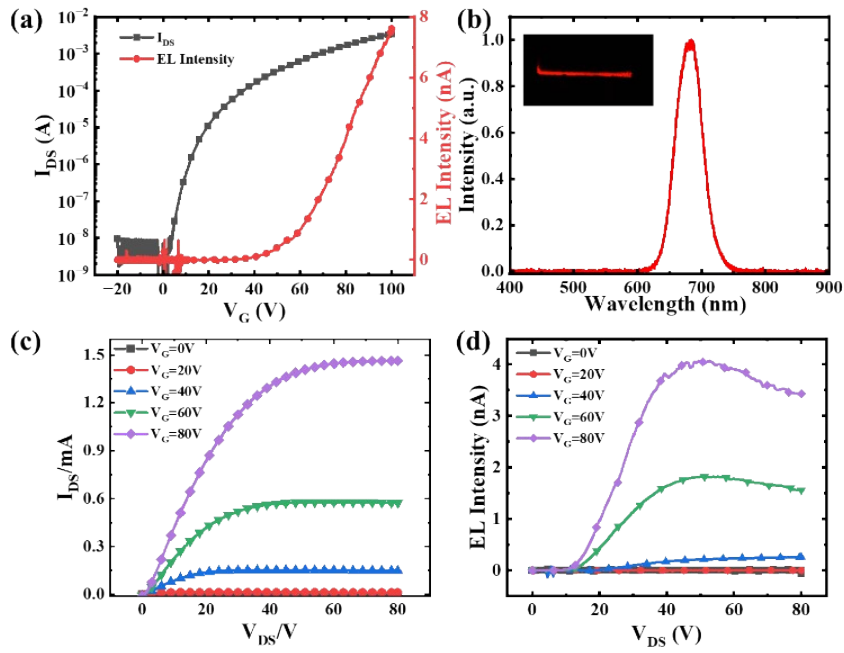


Figure S5. (a) the drain current transfer curve and the electroluminescence intensity transfer characteristics of the fabricated multi-layer LET device based CsPbI₃ QD emissive layer. (b) electroluminescence spectrum of ZTO/CsPbI₃ LET (inset is the picture of line EL along the drain electrode edge next to the channel). (c) electrical output curve of ZTO/CsPbI₃ LET. (d) electroluminescence output curve of ZTO/CsPbI₃ LET.

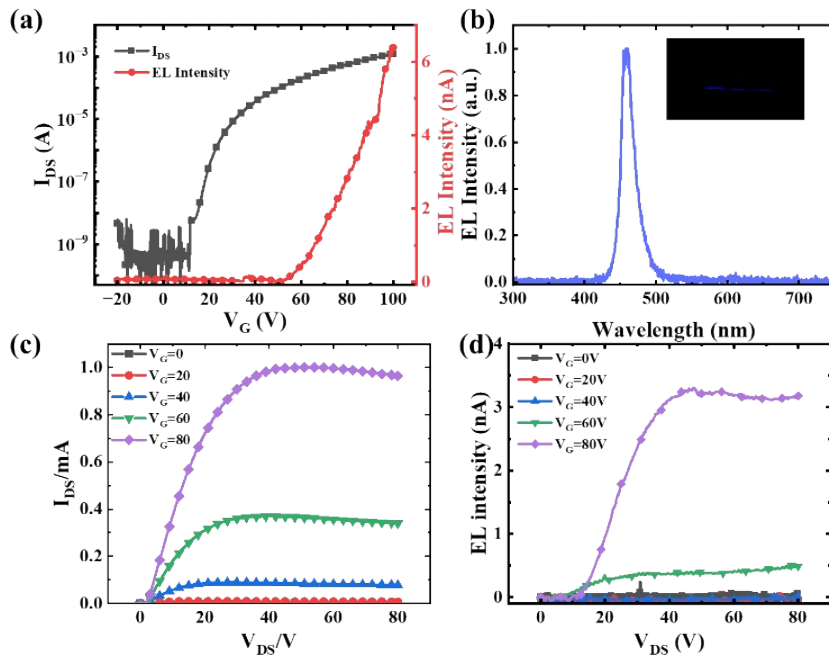


Figure S6. (a) the drain current transfer curve and the electroluminescence intensity transfer characteristics of the fabricated multi-layer LET device based CsPbBr_xCl_{3-x} QD emissive layer. (b) electroluminescence spectrum of ZTO/CsPbBr_xCl_{3-x} LET (inset is the picture of line EL along the drain electrode edge next to the channel). (c) electrical

output curve of ZTO/CsPbBr_xCl_{3-x} LET. (d) electroluminescence output curve of ZTO/CsPbBr_xCl_{3-x} LET.

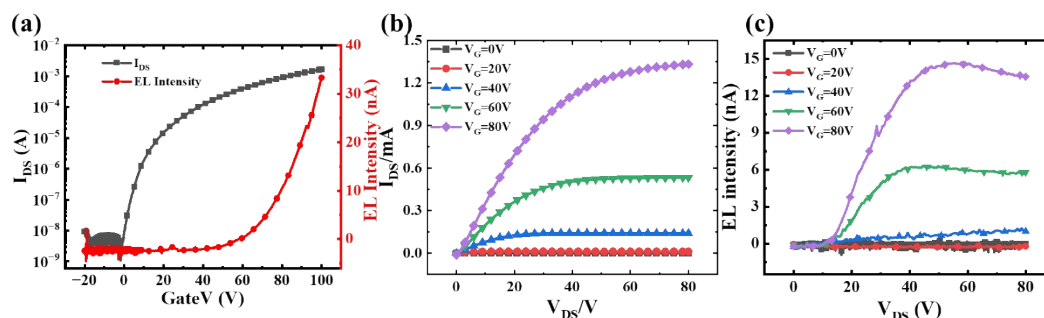


Figure S7. (a) the drain current transfer curve and the electroluminescence intensity transfer characteristics of the fabricated multi-layer area emission LET device based CsPbI₃ emissive layer. (b) electrical output curve. (c) electroluminescence output curve of area emission ZTO/CsPbI₃ LET.

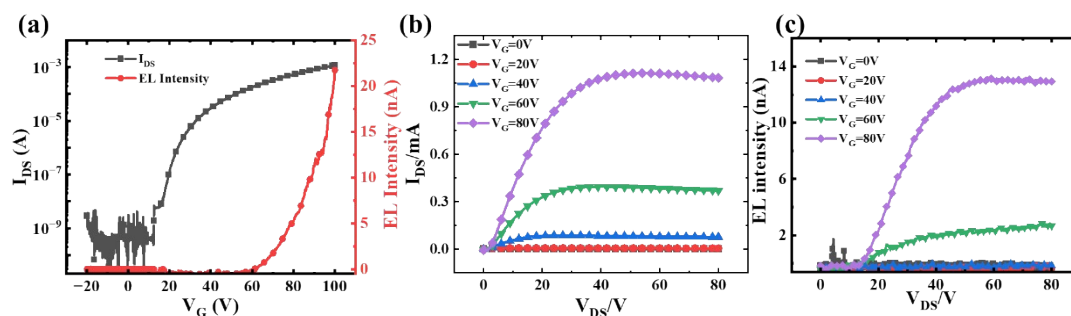


Figure S8. (a) the drain current transfer curve and the electroluminescence intensity transfer characteristics of the fabricated multi-layer area emission LET device based CsPbBr_xCl_{3-x} emissive layer. (b) electrical output curve. (c) electroluminescence output curve of area emission ZTO/CsPbBr_xCl_{3-x} LET.

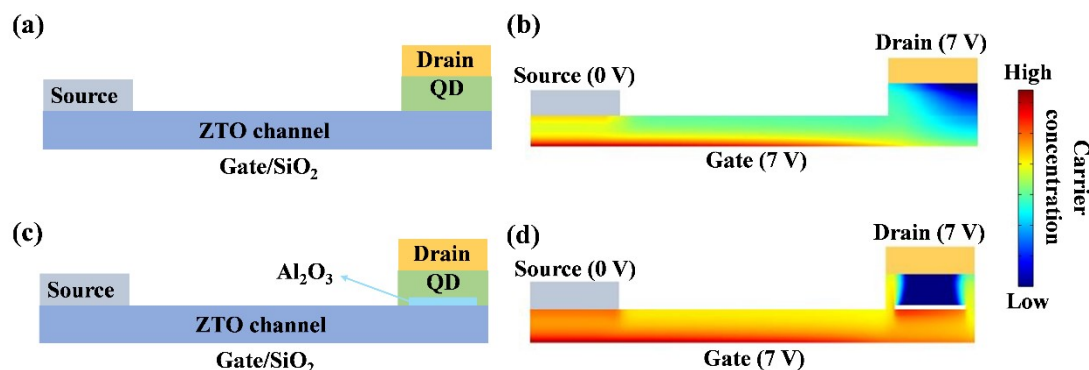


Figure S9. Schematic illustration of (a) the conventional LET device structure and (b) the simulation of its charge carrier distribution; (c) the area emission LET with Al₂O₃(5 nm) device structure and (d) the simulation of its charge carrier distribution.

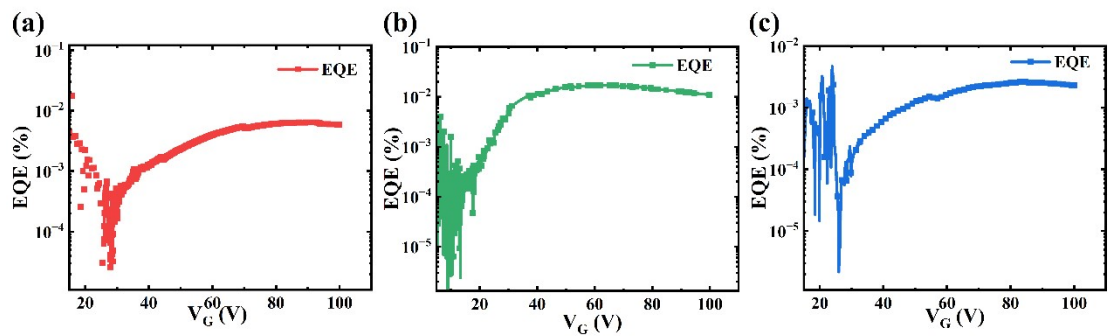


Figure S10. The EQE of the fabricated area emission RGB perovskite LET.

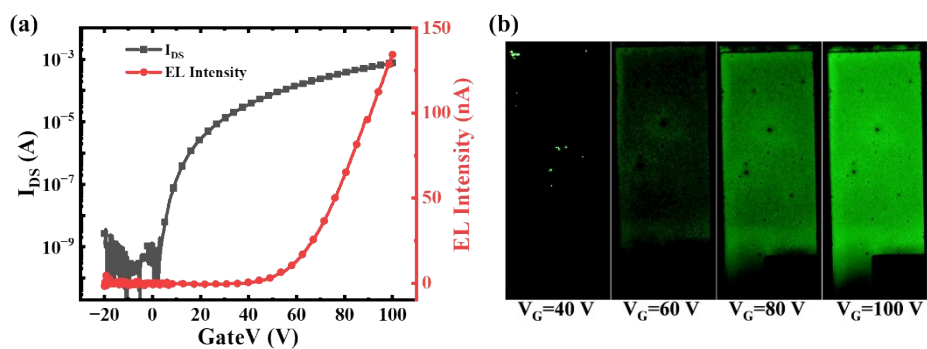


Figure S11. The fabricated multi-layer area emission LET device with 15nm Al_2O_3 layer. (a) the drain current transfer curve and the electroluminescence intensity transfer characteristics. (b) electroluminescence picture at different V_G .